L Number	T72 +-	Coonah Tout	L DD	I m t
T	Hits 1715		DB	Time stamp
	1/15	((118//19) or (414/939) or (156/345.31) or (156/345.32)).CCLS.	USPAT; US-PGPUB	2004/05/04 11:22
_	11	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/30 16:14
1	**	or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	2003/03/30 10:14
		with chamber with remov\$3 with oxide)		
_	152		USPAT;	2003/05/29 20:25
		oxide	US-PGPUB	
-	0	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/29 20:29
İ		or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	
		with chamber with "hf")		
-	260	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/29 20:33
		or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	
_	29	with chamber with (gas vapor)) (((118/719) or (414/939) or (156/345.31)	HCDAM.	2002/05/20 20 41
	. 29	or (156/345.32)).CCLS.) and (transfer\$4	USPAT; US-PGPUB	2003/05/29 20:41
		with chamber with (gas vapor) with	US-EGEUD	
		remov\$3)		
-	2	"11134684"	JPO;	2003/05/29 20:49
			DERWENT	
_	163	sugiura.in. and tokyo.as.	JPO;	2003/05/29 20:49
			DERWENT	
_	. 6	sugiura.in. and tokyo.as. and "uv"	JPO;	2003/05/29 20:49
		/#500000CH #50504C4 #6535555	DERWENT	
_	6		USPAT	2003/05/29 20:53
		"6178660" "6204120" "6232248").PN.		
_	2 0	6178660.URPN. 6467491.URPN.	USPAT	2003/05/29 21:00
_	13	("4795299" "4917556" "5228206"	USPAT USPAT	2003/05/29 21:00 2003/05/29 21:01
		"5423971" "5529657" "5611861"	USPAI	2003/05/29 21:01
		"5755938" "5759334" "5855675"		
		"5863170" "5880924" "5882165"		
]	"5886864").PN.		1
-	112	imahashi.in.	USPAT;	2003/05/30 10:14
	_		US-PGPUB	
-	2	imahashi.in. and 118/719.ccls.	USPAT;	2003/05/30 10:15
		E COEF CA VID DIV	US-PGPUB	
_	50 1715	5695564.URPN.	USPAT	2003/05/30 10:31
	1/13	((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.	USPAT;	2003/05/30 10:38
_	94	(((118/719) or (414/939) or (156/345.31)	US-PGPUB USPAT;	2003/05/30 10:41
		or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	2003/03/30 10:41
		with chamber with (inlet ((vapor gas) with	00 10100	
		suppl\$3)))		
-	· 54		EPO; JPO;	2003/05/30 11:21
		with (inlet suppl\$3) with (vapor gas))	DERWENT	
-	71	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/30 10:51
		or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	
		with chamber with (inlet suppl\$3) with		
_	0	(vapor gas)) (((118/719) or (414/939) or (156/345.31)	HCDAM -	2002/05/20 10 5:
		or (156/345.32)).CCLS.) and ((transfer\$4	USPAT; US-PGPUB	2003/05/30 10:54
		with chamber with (inlet suppl\$3) with	oo-rerub	.
		(vapor gas)) same align\$4)		
_	0	c23c016\$.ipc. and ((transfer\$4 with	EPO; JPO;	2003/05/30 10:54
		chamber with (inlet suppl\$3) with (vapor	DERWENT	111, 10, 00 10.54
	. ,	gas)) same align\$4)		
-	1	c23c016\$.ipc. and ((transfer\$4 with	EPO; JPO;	2003/05/30 10:55
		chamber with (inlet suppl\$3) with (vapor	DERWENT	
_	22	gas)) and align\$4)		
	33	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/30 11:12
		or (156/345.32)).CCLS.) and ((transfer\$4 with chamber with (inlet suppl\$3) with	US-PGPUB	
		(vapor gas)) and align\$4)		
_	. 0	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/30 11:20
		or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	2003,03,30 11.20
		with chamber with (teflon ((silicon with		
İ	ł	carbide) "sic") polytetrafluoroethylene		
	ĺ	<pre>(resin\$3 with polymer\$3)))</pre>		·
-	0	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/05/30 11:21
	}	or (156/345.32)).CCLS.) and (transfer\$4	US-PGPUB	'
		with chamber with (teflon))		

Page 1

	0	or (156/345.32)).CCLS.) and (transfer\$4 with chamber with ((silicon with carbide)	USPAT; US-PGPUB	2003/05/30 11:22
_	0	"sic")) (((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and (transfer\$4 with chamber with polytetrafluoroethylene	USPAT; US-PGPUB	2003/05/30 11:21
_	0)	USPAT; US-PGPUB	2003/05/30 11:22
-	48150	with chamber with resin\$3 with polymer\$3) c23c016\$.ipc.	EPO; JPO;	2003/05/30 16:32
_	0		DERWENT EPO; JPO;	2003/05/30 11:22
_	0	/ and / oramprort i wren	DERWENT EPO; JPO;	2003/05/30 11:24
	0	chamber with ((silicon with carbide) "sic"	DERWENT EPO; JPO; DERWENT	2003/05/30 11:25
_	0	c23c016\$.ipc. and (transfer\$4 with chamber with resin\$3 with polymer\$3)	EPO; JPO; DERWENT	2003/05/30 11:24
-	10		EPO; JPO; DERWENT	2003/05/30 11:22
-	0	c23c016\$.ipc. and (chamber with resin\$3 with polymer\$3)	EPO; JPO; DERWENT	2003/05/30 11:24
	6	polytetrafluoroethylene)	EPO; JPO; DERWENT	2003/05/30 11:24
-	116	((silicon with carbide) "sic"))	EPO; JPO; DERWENT	2003/05/30 11:25
	4	c23c016\$.ipc. and (chamber with ((silicon with carbide) "sic") with corros\$3)	EPO; JPO; DERWENT	2003/05/30 11:25
-	0		USPAT; US-PGPUB	2003/05/30 16:30
_	1	((((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and (transfer\$4 with chamber with "acid")	USPAT; US-PGPUB	2003/05/30 16:14
_	0		USPAT; US-PGPUB	2003/05/30 16:15
-	1		USPAT; US-PGPUB	2003/05/30 16:15
_	1715	((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.	USPAT; US-PGPUB	2003/05/30 18:05
_	670	transfer\$4 with chamber with clean\$3 with (wafer substrate semiconductor)	USPAT; US-PGPUB	2003/05/30 16:36
_	48150	c23c016\$.ipc.	EPO; JPO; DERWENT	2003/05/30 16:32
_	158	transfer\$4 with chamber with clean\$3 with (wafer substrate semiconductor) c23c016\$.ipc. and (transfer\$4 with	EPO; JPO; DERWENT	2003/05/30 16:32
		c23c016\$.ipc. and (transfer\$4 with chamber with clean\$3 with (wafer substrate semiconductor))	USPAT; US-PGPUB	2003/05/30 16:36
_	12	c23c016\$.ipc. and (transfer\$4 with chamber with clean\$3 with (wafer substrate semiconductor))	EPO; JPO; DERWENT	2003/05/30 16:36
-	91	(((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and (transfer\$4 with chamber with clean\$3 with (wafer	USPAT; US-PGPUB	2003/05/30 16:47
	51 6	substrate semiconductor)) 5259881.URPN. ("5228206" "5972161" "6143081" "6178660" "6204120" "6232248").PN.	USPAT USPAT	2003/05/30 17:00 2003/05/30 17:52
- -	- 3 5	5972161.URPN. ("5240556" "5344525" "5554563"	USPAT USPAT	2003/05/30 17:56 2003/05/30 17:58
-	37	"5670421" "5830279").PN. transfer with chamber with ("HF" hydrofluoric)	USPAT;	2003/05/30 18:12
	L	ii A a t a t a a a a a a a a a a a a a a a	US-PGPUB	

Γ	T 5	transfer with chamber with ("HF"	EPO; JPO;	2002/05/20 10:12
	,	hvdrofluoric)		2003/05/30 18:13
•	46	; <u> </u>	DERWENT	2002/05/20 10 15
[-	46	(USPAT;	2003/05/30 18:15
		US-6027960-\$ or US-5939333-\$ or	US-PGPUB;	
		US-5897710-\$ or US-5877086-\$ or	JPO;	
1		US-5271732-\$ or US-5236868-\$ or	DERWENT	
		US-5202275-\$ or US-6467491-\$ or		
		US-5981399-\$ or US-5551984 - \$ or		1
		US-4426439-\$ or US-6178660-\$ or		
		US-5972161-\$ or US-5695564-\$ or		
		US-4883020-\$ or US-5462397-\$ or		
	ļ	US-5474410-\$ or US-5527390 - \$ or	İ	
		US-5740034-\$ or US-5609689-\$ or		
		US-5879461-\$ or US-5882165-\$ or		
		US-6143081-\$ or US-6528431-\$).did. or	}	
	1	(US-6140247-\$ or US-5043299-\$ or		
1	1	US-5259881-\$ or US-5294572-\$ or		
	1	US-6007675-\$ or US-6323463-\$ or		
		US-5770263-\$).did. or (US-20030053893-\$ or	ļ	
		US-20010050146-\$ or US-20010031556-\$ or		1
		US-20010009813-\$ or US-20010001298-\$ or		
		US-20020034595-\$).did. or (JP-2000323425-\$		
	!	or JP-2002270518-\$ or JP-09157073-\$ or		
	,	JP-2002164408-\$).did. or (WO-200070666-\$		1
		or EP-430303-\$ or US-6007675-\$).did.		
l _	18	((US-5766360-\$ or US-4816098-\$ or	USPAT;	2002/05/20 10:04
		US-6027960-\$ or US-5939333-\$ or	US-PGPUB	2003/05/30 18:24
		US-5897710-\$ or US-5877086-\$ or	US-PGPUB	
		US-5271732-\$ or US-5236868-\$ or		
		US-5202275-\$ or US-6467491-\$ or		
				1
		US-5981399-\$ or US-5551984-\$ or		
		US-4426439-\$ or US-6178660-\$ or		
		US-5972161-\$ or US-5695564-\$ or		
		US-4883020-\$ or US-5462397-\$ or		
		US-5474410-\$ or US-5527390-\$ or		
		US-5740034-\$ or US-5609689-\$ or		
		US-5879461-\$ or US-5882165-\$ or		
		US-6143081-\$ or US-6528431-\$).did. or		
		(US-6140247-\$ or US-5043299-\$ or		
ĺ		US-5259881-\$ or US-5294572-\$ or		
	• .	US-6007675-\$ or US-6323463-\$ or		
		US-5770263-\$).did. or (US-20030053893-\$ or		
		US-20010050146-\$ or US-20010031556-\$ or		1
		US-20010009813-\$ or US-20010001298-\$ or		
		US-20020034595-\$).did. or (JP-2000323425-\$		
		or JP-2002270518-\$ or JP-09157073-\$ or]
ĺ		JP-2002164408-\$).did. or (WO-200070666-\$		1
		or EP-430303-\$ or US-6007675-\$).did.) and		
		(oxide with (remov\$3 clean\$3) with		
		chamber)		
				ı l

-	3	1 (100 0.00000 4 02 00 10-0000 1 02	USPAT;	2003/05/30 18:24
		US-6027960-\$ or US-5939333-\$ or	US-PGPUB	
		US-5897710-\$ or US-5877086-\$ or		
		US-5271732-\$ or US-5236868-\$ or		
ļ		US-5202275-\$ or US-6467491-\$ or		
		US-5981399-\$ or US-5551984-\$ or		
		US-4426439-\$ or US-6178660-\$ or		
		US-5972161-\$ or US-5695564-\$ or		
]	US-4883020-\$ or US-5462397-\$ or		
		US-5474410-\$ or US-5527390-\$ or		
		US-5740034-\$ or US-5609689-\$ or		
		US-5879461-\$ or US-5882165-\$ or		
		US-6143081-\$ or US-6528431-\$).did. or		
		(US-6140247-\$ or US-5043299-\$ or		
		US-5259881-\$ or US-5294572-\$ or		
		US-6007675-\$ or US-6323463-\$ or		
		US-5770263-\$).did. or (US-20030053893-\$ or		•
		US-20010050146-\$ or US-20010031556-\$ or		·
Ì		US-20010009813-\$ or US-20010001298-\$ or		
		US-20020034595-\$).did. or (JP-2000323425-\$) or JP-2002270518-\$ or JP-09157073-\$ or		
	1	JP-2002164408-\$).did. or (WO-200070666-\$		
		or EP-430303-\$ or US-6007675-\$).did.) and		
		(transfer\$3 same rotat\$3 same align\$3)		
_	0		EPO; JPO;	2003/06/02 08:30
	1	with plural\$3 with (even\$3))	DERWENT	2003/00/02 08:30
1 -	2	(transfer with chamber) same (outlet with	USPAT;	2003/06/02 08:22
		plural\$3 with (even\$3))	US-PGPUB	2003/00/02 00:22
-	1715		USPAT;	2003/06/02 08:23
		(156/345.32)).CCLS.	US-PGPUB	
_	0	("5 and ((gas vapor) with (plural\$3	USPAT;	2003/06/02 08:28
i		multipl\$3) with even\$3)").PN.	US-PGPUB	2000, 00, 02 00.20
-	16		USPAT;	2003/06/02 08:27
		or (156/345.32)).CCLS.) and ((gas vapor)	US-PGPUB	
	ļ	with (plural\$3 multipl\$3) with even\$3)		
-	145	(118/\$.ccls. 156/345.\$.ccls.) and ((gas	USPAT;	2003/06/02 08:28
		vapor) with (plural\$3 multipl\$3) with	US-PGPUB]
		even\$3)		
-	175	(c23c016\$.ipc. h011021\$.ipc.)and ((gas	USPAT;	2003/06/02 08:28
		vapor) with (plural\$3 multipl\$3) with	US-PGPUB	
		even\$3)		f I
-	0	(c23c016\$.ipc. h011021\$.ipc.)and ((gas	EPO; JPO;	2003/06/02 08:30
		vapor) with (plural\$3 multipl\$3) with	DERWENT	
		even\$3)		
-	0	(c23c016\$.ipc. h011021\$.ipc.)and ((gas	EPO; JPO;	2003/06/02 08:29
		vapor) with (plural\$3 multipl\$3) with	DERWENT	
1	_	(outlet inlet hole orifice))		
-	0	(c23c016\$.ipc. h011021\$.ipc.)and ((gas	EPO; JPO;	2003/06/02 08:29
		vapor) same (plural\$3 multipl\$3) same	DERWENT	
	1	(outlet inlet hole orifice))		
-	0	(() and () did	EPO; JPO;	2003/06/02 08:29
		vapor) same (plural\$3 multipl\$3) same	DERWENT	
1_	40150	(outlet inlet hole orifice))		0000106100 00 55
-	48150	c23c016\$.ipc.	EPO; JPO;	2003/06/02 08:30
_	742155	h0110216 inc	DERWENT	2002/06/00 00 00
-	742155	h011021\$.ipc.	EPO; JPO;	2003/06/02 08:30
_	0	(c23c016\$.ipc. h011021\$.ipc.) same (outlet	DERWENT	2002/06/02 22 12
1	1		EPO; JPO;	2003/06/02 09:10
_	5	with plural\$3 with (even\$3)) (c23c016\$.ipc. h011021\$.ipc.) and (outlet	DERWENT	2002/06/02 00:21
		with plural\$3 with (even\$3))	EPO; JPO; DERWENT	2003/06/02 08:31
_	82		EPO; JPO;	2003/06/02 08:32
	1	vapor) with (plural\$3 multipl\$3) with	DERWENT	2003/00/02 00:32
		even\$3)	~DEC-11011	
-	70	118/\$.ccls. and (oxide with remov\$3)	EPO; JPO;	2003/06/02 09:11
		(Total and fontae natin temovy)	DERWENT	2000,00,02 05.11
_	667	118/\$.ccls. and (oxide with remov\$3)	USPAT;	2003/06/02 09:11
	""	, , , soro, and , ontae mach temovys,	US-PGPUB	2000,00,02 07.11
-	159	118/\$.ccls. and (oxide with remov\$3 with	USPAT;	2003/06/02 09:12
		chamber)	US-PGPUB	
1 -	27	118/\$.ccls. and (oxide with remov\$3 with	USPAT;	2003/06/02 09:13
		chamber with transfer\$4)	US-PGPUB	

				•
-	151	((transfer\$4 transport\$4) with chamber with (substrate wafer semiconductor) with	EPO; JPO; DERWENT	2003/11/20 13:49
_	624	(vapor\$4)) ((transfer\$4 transport\$4) with chamber with (substrate wafer semiconductor) with	USPAT; US-PGPUB	2003/11/20 13:38
-	68	<pre>(vapor\$4)) ("transfer chamber" with (substrate wafer semiconductor) with (vapor\$4))</pre>	USPAT; US-PGPUB	2003/11/20 13:38
_	17	((transfer\$4 adj chamber) with (substrate	EPO; JPO;	2003/11/20 14:26
-	0	<pre>wafer semiconductor) with (vapor\$4)) ("transfer\$4 chamber" with (vapor\$4))</pre>	DERWENT EPO; JPO; DERWENT	2003/11/20 14:01
-	161	("transfer chamber" with (vapor\$4))	USPAT; US-PGPUB	2003/11/20 14:21
-	37	("transfer chamber" with (vapor\$4) with (expos\$3 introduc\$3 inlet outlet supplied supply\$3))	USPAT; US-PGPUB	2003/11/20 14:04
_	124	<pre>(("transfer chamber" with (vapor\$4))) not (("transfer chamber" with (vapor\$4) with (expos\$3 introduc\$3 inlet outlet supplied supply\$3)))</pre>	USPAT; US-PGPUB	2003/11/20 14:21
	1811	((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.	USPAT; US-PGPUB	2003/11/20 15:04
-	8	(vapor with (supply\$3 suppli\$3) with transfer\$4) and (((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.)	USPAT; US-PGPUB	2003/11/20 14:25
-	0	"vapor inlet" with "transfer chamber",	EPO; JPO; DERWENT	2003/11/20 14:27
_	0	"vapor inlet" with "transfer chamber"	USPAT; US-PGPUB	2003/11/20 14:27
_	1	"vapor port" with "transfer chamber"	USPAT; US-PGPUB	2003/11/20 14:27
-	0	"vapor hole" with "transfer chamber"	USPAT; US-PGPUB	2003/11/20 14:27
_	5	"vapor outlet" with "transfer chamber"	USPAT; US-PGPUB	2003/11/20 14:28
	5	<pre>(vapor\$4 adj (inlet hole port outlet conduit entrance introduc\$3 outlet aperture opening exit orifice vent\$3)) with "transfer chamber"</pre>	USPAT; US-PGPUB	2003/11/20 14:31
-	6	("4490209" "5007982" "5605603" "5854137" "5874362" "6242350").PN.	USPAT	2003/11/20 14:32
-	6	<pre>(vapor\$4 with (inlet hole port outlet conduit entrance introduc\$3 outlet aperture opening exit orifice vent\$3))</pre>	EPO; JPO; DERWENT	2003/11/20 14:34
_	25	with "transfer chamber" (vapor\$4 with (inlet hole port outlet conduit entrance introduc\$3 outlet aperture opening exit orifice vent\$3) with transfer\$4) and c23c016\$.ipc.	EPO; JPO; DERWENT	2003/11/20 14:41
_	32	427/335.ccls.	EPO; JPO; DERWENT	2003/11/20 14:42
-	3	427/335.ccls. and (transfer\$3 with chamber)	USPAT; US-PGPUB	2003/11/20 14:42
_	208	427/335.ccls.	USPAT; US-PGPUB	2003/11/20 14:45
_	19	(((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and (("hydrofluoric acid" "hf") with vapor\$4)	USPAT; US-PGPUB	2003/11/20 15:55
_	2	118/719.ccls. and imahashi.in.	USPAT; US-PGPUB	2003/11/20 15:00
-	0	(((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and ("transfer chamber" with (vaporiser vaporizer))	USPAT; US-PGPUB	2003/11/20 15:05
-	0	(((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and (transfer\$3 with chamber with (vaporiser vaporizer))	USPAT; US-PGPUB	2003/11/20 15:07
_	10	(((118/719) or (414/939) or (156/345.31) or (156/345.32)).CCLS.) and (transfer\$3 with chamber with remov\$4 with oxide)	USPAT; US-PGPUB	2003/11/20 15:09

-	39	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:09
• •		or (156/345.32)).CCLS.) and (transfer\$3	US-PGPUB	
	,	with chamber with oxide)		
-	16	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:14
		or (156/345.32)).CCLS.) and ("transfer	US-PGPUB	
		chamber" with oxide)		
_	92	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:18
-		or (156/345.32)).CCLS.) and ("transfer	US-PGPUB	
		chamber" with gas)		
_	9	c23c016\$.ipc. and ("transfer chamber"	EPO; JPO;	2003/11/20 15:19
		with (remov\$3 clean\$3))	DERWENT	
-	79.	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:49
		or (156/345.32)).CCLS.) and ("transfer	US-PGPUB	
1 .		chamber" with (remov\$3 clean\$3))		
Í –	6	("5228206" "5972161" "6143081"	USPAT	2003/11/20 15:38
		"6178660" "6204120" "6232248").PN.		
-	3	5972161.URPN.	USPAT	2003/11/20 15:39
-	0	6467491.URPN.	USPAT	2003/11/20 15:39
-	13	("4795299" "4917556" "5228206"	USPAT	2003/11/20 15:42
		"5423971" "5529657" "5611861"		
		"5755938" "5759334" "5855675"		
		"5863170" "5880924" "5882165"		
		"5886864").PN.	•	
-	0	6467491.URPN.	USPAT	2003/11/20 15:43
·-	6		USPAT	2003/11/20 15:43
l ,		"6178660" "6204120" "6232248").PN.		
-	11	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:51
,		or (156/345.32)).CCLS.) and ("transfer	US-PGPUB	1
]		chamber" with etch)	,	
-	0	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:52
		or (156/345.32)).CCLS.) and ("transfer	US-PGPUB	
l		chamber" with "pre-process")	ŀ	
-	3	(((===, ===, == (===, ===, == (===, =====, ====,	USPAT;	2003/11/20 15:52
.		or (156/345.32)).CCLS.) and ("transfer	US-PGPUB	
		<pre>chamber" with "pre-processing")</pre>	1	·
-	0	(((118/719) or (414/939) or (156/345.31)	USPAT;	2003/11/20 15:58
i l		or (156/345.32)).CCLS.) and	US-PGPUB	
		(("hydrofluoric acid" "hf") with "transfer		
		chamber")		
] -	195	118/\$.ccls. and (transfer\$4 with chamber	USPAT;	2003/11/20 15:59
.		with expos\$4)	US-PGPUB	
-	49	118/\$.ccls. and (transfer\$4 adj chamber	USPAT;	2003/11/20 15:59
	, ,	with expos\$4)	US-PGPUB	
=	49	118/\$.ccls. and ((transfer\$4 adj chamber)	USPAT;	2003/11/20 16:04
	ا ۔	with expos\$4)	US-PGPUB	
-	. 1	118/\$.ccls. and ((transfer\$4 adj chamber)	USPAT;	2003/11/20 16:04
	_	with acid)	US-PGPUB	
-	1	("5043299").PN.	USPAT;	2003/11/21 10:55
			US-PGPUB	

		1 (110 FR CC) CO A	1	T	
-	64	(11 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	USPAT;	2003/11/21	13:22
		US-6528431-\$ or US-6140247-\$ or	US-PGPUB;		
1	ŀ	US-6027960-\$ or US-5939333-\$ or	JPO;		
		US-5897710-\$ or US-5877086-\$ or	DERWENT		
		US-5271732-\$ or US-5236868-\$ or			
		US-5202275-\$ or US-5043299-\$ or			
	İ	US-6467491-\$ or US-6083566-\$ or			
		US-5981399-\$ or US-5551984-\$ or			
		US-4883020-\$ or US-4426439-\$ or			
		US-6178660-\$ or US-6143081-\$ or			
,		US-5972161-\$ or US-5882165-\$ or			
		US-5695564-\$ or US-6183564-\$ or			
		US-5879461-\$ or US-5740034-\$).did. or			
		(US-5609689-\$ or US-5527390-\$ or			
		US-5474410-\$ or US-5462397-\$ or			
		US-6039811-\$ or US-6007675-\$ or		,	
		US-5294572-\$ or US-5259881-\$ or	1	1	
		US-6323463-\$ or US-5770263-\$ or			
		US-4565157-\$ or US-4262631-\$ or			
		US-5314574-\$ or US-6578589-\$ or			
1		US-6221742-\$ or US-6132564-\$ or			
		US-6358859-\$ or US-4386119-\$ or		}	
	1	US-4834020-\$).did. or (US-20030053893-\$ or	1		
	1	US-20010031556-\$ or US-20010009813-\$ or	1		•
		US-20010001298-\$ or US-20010050146-\$ or]]	
		US-20020034595-\$ or US-20020069899-\$ or US-20020020429-\$ or US-20010017103-\$ or	1		
		US-20020184896-\$).did. or (JP-2000323425-\$			
		or JP-2002270518-\$ or JP-09157073-\$ or			
		JP-2002164408-\$ or JP-61054628-\$).did. or	ļ		
1		(WO-200070666-\$ or US-6007675-\$ or		-	
		EP-430303-\$ or US-20010031556-\$).did.			
_	291		ticnam.	2002/11/21	11.02
1	231	with chamber with vapor\$4)	USPAT; US-PGPUB;	2003/11/21	11:03
	1	with chamber with vapor44)	•		
	1		JPO;		
_	38	(427/\$.ccls. 438/\$.ccls.) and ((transfer\$4	DERWENT USPAT;	2003/11/21	11.02
		adj chamber) with vapor\$4)	US-PGPUB;	2003/11/21	11:03
		day chamber, with vaporva,	JPO;		
			DERWENT		
_	40	(427/\$.ccls. 438/\$.ccls.) and ((transfer\$4	USPAT;	2003/11/21	11.10
	1	adj chamber) with (vapor\$4 "hf"	US-PGPUB;	2003/11/21	11:19
1		"hydrofluoric" "hydrogen fluoride"))	JPO;		j
		injurogen riuoriue //	DERWENT		
_	6	("4490209" "5007982" "5605603"	USPAT	2003/11/21	11.11
	1	"5854137" "5874362" "6242350").PN.	001111	2003/11/21	
-	1		USPAT;	2003/11/21	11:21
1		adj chamber) with ("etching gas"))	US-PGPUB;		
		, , , , , , , , , , , , , , , , , , ,	JPO;		
			DERWENT		
-	1	(427/\$.ccls. 438/\$.ccls.) and ((transfer\$4	USPAT;	2003/11/21	11:23
		adj chamber) with (etch\$3 with (while	US-PGPUB	= +, - +	
		during)))			
-	25		USPAT;	2003/11/21	11:24
		adj chamber) with (remov\$3 with (layer	US-PGPUB		l
1		film coating)))			
-	8	(118/715-733.ccls. 156/345.\$.ccls.) and	USPAT;	2003/11/21	11:29
	[((transfer\$4 adj chamber) with (remov\$3	US-PGPUB		
J		<pre>with (layer film coating)))</pre>			1
-	44	5314574.URPN.	USPAT	2003/11/21	
-	4	("4654106" "4857142" "5169408"	USPAT	2003/11/21	11:49
	_	"5248380").PN.	ĺ		
_	0	"09758610"	USPAT;	2003/11/21	12:37
	_	H00 /750 -610H	US-PGPUB		
_	1	"09/758,610"	USPAT;	2003/11/21	12:41
_		(#6179660#) DN	US-PGPUB	0000 /44 /04	10
] -	1	("6178660").PN.	USPAT;	2003/11/21	12:41
	L		US-PGPUB		l

-	2	((USPAT;	2003/11/21 14:02
		US-6528431-\$ or US-6140247-\$ or	US-PGPUB;	
		US-6027960-\$ or US-5939333-\$ or	JPO;	
		US-5897710-\$ or US-5877086-\$ or	DERWENT	1
		US-5271732-\$ or US-5236868-\$ or		
		US-5202275-\$ or US-5043299-\$ or		
		US-6467491-\$ or US-6083566-\$ or		
1		US-5981399-\$ or US-5551984-\$ or	1	
		US-4883020-\$ or US-4426439-\$ or		
		US-6178660-\$ or US-6143081-\$ or		1
ł		US-5972161-\$ or US-5882165-\$ or		
		US-5695564-\$ or US-6183564-\$ or		
	ĺ	US-5879461-\$ or US-5740034-\$).did. or		i
[(US-5609689-\$ or US-5527390-\$ or		
		US-5474410-\$ or US-5462397-\$ or		
-	İ	US-6039811-\$ or US-6007675-\$ or		1
	1 .			
	•	US-5294572-\$ or US-5259881-\$ or		i
ļ	}	US-6323463-\$ or US-5770263-\$ or		
1		US-4565157-\$ or US-4262631-\$ or		1
		US-5314574-\$ or US-6578589-\$ or		
ļ	1	US-6221742-\$ or US-6132564-\$ or		
		US-6358859-\$ or US-4386119-\$ or		1
		US-4834020-\$).did. or (US-20030053893-\$ or	1]
Į.		US-20010031556-\$ or US-20010009813-\$ or		1
1		US-20010001298-\$ or US-20010050146-\$ or		.
		US-20020034595-\$ or US-20020069899-\$ or		
	1	US-20020020429-\$ or US-20010017103-\$ or		
		US-20020184896-\$).did. or (JP-2000323425-\$		
		or JP-2002270518-\$ or JP-09157073-\$ or		
		JP-2002164408-\$ or JP-61054628-\$).did. or		
		(WO-200070666-\$ or US-6007675-\$ or		İ
		EP-430303-\$ or US-20010031556-\$).did.) and		
		(transfer with chamber with align)		
-	0	pas-sylvia.in.	USPAT;	2003/11/21 14:02
1		·	US-PGPUB;	1
			JPO;	1
			DERWENT	
-	1	pas-sylvia-h.in.	USPAT;	2003/11/21 14:03
	_		US-PGPUB	1
_	3	pas-sylvia-\$.in.	USPAT;	2003/11/21 14:03
			US-PGPUB	
-	1	("6391148").PN.	USPAT;	2003/11/21 15:09
			US-PGPUB	1
_	29	("transfer chamber" "transferring	EPO; JPO;	2004/05/04 11:23
		chamber") with vapor\$3	DERWENT	f
-	174	("transfer chamber" "transferring	USPAT;	2004/05/04 12:00
		chamber") with vapor\$3	US-PGPUB	
-	116	(("transfer chamber" "transferring	USPAT;	2004/05/04 12:02
		chamber") with vapor\$3) and (substrate	US-PGPUB	
		wafer semiconductor)		
-	117	(("transfer chamber" "transferring	USPAT;	2004/05/04 12:03
		chamber") with vapor\$3) and (substrate	US-PGPUB	
		wafer workpiece semiconductor)		
-	0	(((vapor\$3 with solution) bubbler) with	USPAT;	2004/05/04 12:05
		(transfer\$3 adj chamber)) and (414/\$.ccls.	US-PGPUB	
	ļ	118/\$.ccls. 216/\$.ccls. 427/\$.ccls.)		1
-	8	(((vapor\$3 with solution) bubbler) with	USPAT;	2004/05/04 12:08
		(transfer\$3 adj chamber))	US-PGPUB	
-	8	(((vapor\$3 with solution) bubbler) with	USPAT;	2004/05/04 12:08
		(transfer\$4 adj chamber))	US-PGPUB	
-	8	(((vapor\$3 with solution) bubbler) with	USPAT;	2004/05/04 12:08
]	(transfer\$4 adj chamber))	US-PGPUB	. ==2,
-	4	(((vapor\$3 with solution) bubbler) with	EPO; JPO;	2004/05/04 12:10
	[(transfer\$4 adj chamber))	DERWENT	
-	180	(((solution)) with (transfer\$4 adj	EPO; JPO;	2004/05/04 12:10
		chamber))	DERWENT	
-	116	(((solution)) with (transfer\$4 adj	EPO; JPO;	2004/05/04 12:28
		chamber)) and (substrate workpiece wafer	DERWENT	
	[semiconductor)		
-	127	(gas\$4 with (transfer\$4 adj chamber)) and	EPO; JPO;	2004/05/04 12:11
	1	(substrate workpiece wafer semiconductor)	DERWENT	, ,
		Todoscrace workpreed warer semirounductor,		

			•	
-	14	(gas\$4 with solution with (transfer\$4 adj chamber)) and (substrate workpiece wafer	EPO; JPO; DERWENT	2004/05/04 12:27
-	0	chamber)) and (substrate workpiece wafer	USPAT; US-PGPUB	2004/05/04 12:15
_	37	and (substrate workpiece wafer	USPAT; US-PGPUB	2004/05/04 12:16
_	3	semiconductor) 5983909.URPN.	USPAT	2004/05/04 12:19
-	3 4	5983909.URPN. ("5599438" "5616221" "5635053" "5676760").PN.	USPAT USPAT	2004/05/04 12:19 2004/05/04 12:19
-	11 6	6039815.URPN. ("5190627" "5599438" "5616221"	USPAT USPAT	2004/05/04 12:20 2004/05/04 12:21
_	0	"5635053" "5676760" "5806126").PN. "vaporous solution"	EPO; JPO;	2004/05/04 12:27
_	0	(bubbler with (transfer\$4 adj chamber)) and (substrate workpiece wafer	DERWENT EPO; JPO; DERWENT	2004/05/04 12:29
-	1	semiconductor)	USPAT;	2004/05/04 12:28
-	0	semiconductor) (vapor with (transfer\$4 adj chamber) with	US-PGPUB EPO; JPO;	2004/05/04 12:30
		("HF" "HBR" "HCL")) and (substrate workpiece wafer semiconductor)	DERWENT	
_	1	((transfer\$4 adj chamber) with ("HF" "HBR" "HCL")) and (substrate workpiece wafer semiconductor)	EPO; JPO; DERWENT	2004/05/04 12:31
_	5		USPAT; US-PGPUB	2004/05/04 12:32
_	0	((transfer\$4 adj chamber) with vapor with (liquid aqueous)) and (substrate workpiece	EPO; JPO; DERWENT	2004/05/04 12:33
-	4	<pre>wafer semiconductor) ((transfer\$4 adj chamber) with vapor with (liquid aqueous)) and (substrate workpiece wafer semiconductor)</pre>	USPAT; US-PGPUB	2004/05/04 12:34
-	195		USPAT; US-PGPUB	2004/05/04 13:24
-	397	(((transfer\$4 transport\$3) adj chamber) with (clean\$3)) and (substrate workpiece wafer semiconductor)	USPAT; US-PGPUB	2004/05/04 13:25
_	8		USPAT; US-PGPUB	2004/05/04 13:28
-	397	((transfer\$4 transport\$3) adj chamber) with (clean\$3)) and (substrate workpiece wafer semiconductor)	USPAT; US-PGPUB	2004/05/04 13:28
-	45	5314574.URPN.	USPAT	2004/05/04 13:31
-	116	(156/345.31.ccls. 156/345.32.ccls. 414/935-939.ccls. 118/719.ccls. 204/298.25.ccls. 204/298.26.ccls.	USPAT; US-PGPUB	2004/05/04 14:48
		204/298.35.ccls.) and (((transfer\$4 transport\$3) adj chamber) same (solution aqueous liquid vapor\$3))		
-	764	"hf vapor"	USPAT; US-PGPUB	2004/05/04 14:48
-	34	"hf vapor" and ((transfer\$4 transport\$3) adj chamber)	USPAT; US-PGPUB	2004/05/04 14:48
_	0	"hbr vapor" and ((transfer\$4 transport\$3) adj chamber) ("hbr vapor" "hbr vapor" "hgl vapor") with	USPAT; US-PGPUB	2004/05/04 14:48
-	3	("hbr vapor" "hbr vapor" "hcl vapor") with ((transfer\$4 transport\$3) adj chamber) ("hbr vapor" "hbr vapor" "hcl vapor") with	USPAT; US-PGPUB USPAT;	2004/05/04 14:49 2004/05/04 14:53
-	0	(transfer\$4 transport\$3) with chamber ("hbr vapor" "hbr vapor" "hcl vapor") with	US-PGPUB EPO; JPO;	2004/05/04 14:52
-	5	(transfer\$4 transport\$3) with chamber ("hbr" "hbr" "hcl") with vapor with	DERWENT USPAT;	2004/05/04 14:53
		(transfer\$4 transport\$3) with chamber	US-PGPUB	

			*	
_	5		USPAT;	2004/05/04 14:56
.	İ	(transfer\$4 transport\$3) with chamber	US-PGPUB	
_	6		USPAT	2004/05/04 14:55
		"5854137" "5874362" "6242350").PN.		1111,111,111
-	1		EPO; JPO;	2004/05/04 14:57
		(transfer\$4 transport\$3) with chamber	DERWENT	2001/00/01 11.9/
_	8	(acid\$2) with vapor\$5 with (transfer\$4	EPO; JPO;	2004/05/04 15:05
		transport\$3) with chamber	DERWENT	2004/03/04 13:03
_	28	(acid\$2) with vapor\$5 with (transfer\$4	USPAT;	2004/05/04 15:43
1		transport\$3) with chamber	US-PGPUB	2004/03/04 15.45
_	404	kondo.in. and oxide and vapor	USPAT;	2004/05/04 15:43
			US-PGPUB	2001/03/04 13:43
-	83	kondo.in. and oxide and vapor	EPO; JPO;	2004/05/04 15:43
		1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	DERWENT	2001/03/04 13:43
l –	47	kondo.in. and oxide and vapor and	EPO; JPO;	2004/05/04 15:44
		(substrate wafer semiconductor workpiece)	DERWENT	2001/05/01 15:11
-	8	kondo.in. and oxide and vapor and	EPO; JPO;	2004/05/04 15:49
Ì		(substrate wafer semiconductor workpiece)	DERWENT	2001703704 13.43
		and acid\$3	DERWENT	
-	182	kondo.in. and oxide and vapor and	USPAT;	2004/05/04 15:49
1		(substrate wafer semiconductor workpiece)	US-PGPUB	2004/05/04 15:49
		and acid\$3	00 10102	. [
-	4	kondo.in. and (oxide same vapor same	USPAT;	2004/05/04 15:52
		(substrate wafer semiconductor workpiece)	US-PGPUB	2004/03/04 13.32
	İ	same acid\$3)	00 10105	
-	43	1	USPAT	2004/05/04 15:51
-	1	"4592306".PN.	USPAT	2004/05/04 15:51
-	0	(("hbr vapor" "hbr vapor" "hcl vapor")	USPAT;	2004/05/04 15:53
	}	with (transfer\$4 transport\$3) with	US-PGPUB	2001,03,04 13.33
Ì		chamber) and (vapor\$3 same acid\$3)	10102	
	0	(("hbr vapor" "hbr vapor" "hcl vapor")	USPAT;	2004/05/04 15:52
		with (transfer\$4 transport\$3) with	US-PGPUB	= 3 3 7 3 3 7 3 3 3 3 5 3 5 5 5 5 5 5 5 5
		chamber) and (acid\$3)		1 .
-	0	((("hbr vapor" "hbr vapor" "hcl vapor")	USPAT;	2004/05/04 15:52
		with (transfer\$4 transport\$3) with	US-PGPUB	2001,,00,01 10.02
ļ		chamber) and (vapor\$3 same acid\$3)) and (ì
		vapor\$3 same acid\$3)		,
-	2	5303671.URPN. and (vapor\$3 same acid\$3)	USPAT;	2004/05/04 15:53
			US-PGPUB	
_	7	5303671.URPN. and (acid\$3)	USPAT;	2004/05/04 15:55
	. 1		US-PGPUB	
-	18	5303671.URPN. and (vapor\$3)	USPAT;	2004/05/04 15:56
	•		US-PGPUB	
-	2	5303671.URPN. and (vapor\$3 with	USPAT;	2004/05/04 17:00
		(transfer\$4 transport\$4))	US-PGPUB	
_	1	"4592306".PN.	USPAT	2004/05/04 16:10
_	43	5303671.URPN.	USPAT	2004/05/04 16:10
_	1	10/265,899	USPAT;	2004/05/04 17:01
			US-PGPUB	
-	1	10/265,699	USPAT;	2004/05/04 17:01
			US-PGPUB	
_	1	414/936.ccls. and (vapor\$3 with (acid "HF"	USPAT;	2004/05/05 12:16
		"Hbr" "HCL"))	US-PGPUB	
_	11	5474641.URPN.	USPAT	2004/05/05 12:27
-	173	(oxide with remov\$3) with transfer\$4 with	USPAT;	2004/05/05 12:16
	l.	chamber	US-PGPUB	